

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|--|---|------------------|---------|------------------|
| L4 | 832 | ((fluid or gas) near3 (clean\$3 or purg\$3)) with (lens or (project\$3 near optical)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:05 |
| L5 | 76965 | (substrate or wafer) and (mask or reticle) and (lithography or photolithography or (micro near lithography)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:36 |
| L6 | 132 | 4 and 5 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:36 |
| L7 | 220919 | (radiation or illumination or lamp or light) with (fluid or gas) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:37 |
| L8 | 220919 | (radiation or illumination or lamp or light) with (fluid or gas) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:38 |
| L9 | 121 | 8 and 6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:37 |
| L10 | 6091 | (radiation or illumination or lamp or light) with (fluid or gas) with (clean\$3 or purg\$3 or dissociat\$3) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:38 |
| L11 | 108 | 10 and 6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/10/28 13:38 |

PK 10/28/05

Interference Search

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|---|----------|------------------|---------|------------------|
| L1 | 2 | ((fluid or gas) near3 (clean\$3 or purg\$3 or dissociat\$3)) and (radiation or illumination or lamp or light) and (nucleat\$3 near (site or surface))).clm. | US-PGPUB | OR | ON | 2005/10/28 17:25 |

OK
10/28/05